

Customer No.: 31561
Docket No.: 13304-US-PA
Application No.: 10/710,599

AMENDMENTS

IN THE CLAIMS:

Claim 1. (currently amended) A method of manufacturing a color filter array, comprising the steps of:

(a) forming a patterned first photoresist layer over a substrate, wherein the first photoresist layer has a plurality of openings with each opening exposing a portion of the substrate;

(b) forming a filter material layer over the exposed substrate within the openings and the first photoresist layer;

(c) forming a second photoresist layer over the filter material layer within the openings and exposing the filter material layer over the first photoresist layer;

(d) removing the filter material layer over the first photoresist layer;

[(e)] [(e)] (e) removing the first photoresist layer and the second photoresist layer to form a plurality of first color filter films; and

[(f)] [(f)] (f) repeating the steps from (a) to [(c)] (d) at least once and removing the first photoresist layer and the second photoresist layer to form a plurality of second color filter films on the substrate in areas except the first color filter films.

Claims 2-3 (canceled)

Claim 4. (currently amended) The method of claim 1, wherein the filter material layer has a thickness smaller than the first photoresist layer such that the filter material layer within the openings is separated from the filter material layer over the first

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photoresist layer.

Claim 5. (original) The method of claim 1, wherein the filter material layer has a thickness equal to the first photoresist layer.

Claim 6. (currently amended) A method of manufacturing a thin film on a substrate, comprising the steps of:

(a) forming a patterned first photoresist layer over the substrate, wherein the first photoresist layer has a plurality of openings with each opening exposing a portion of the substrate;

(b) forming a filter material layer over the exposed substrate within the openings and the first photoresist layer;

(c) forming a second photoresist layer over the filter material layer within the openings and exposing the filter material layer over the first photoresist layer;

(d) removing the filter material layer over the first photoresist layer;

[(d)] (e) removing the first photoresist layer and the second photoresist layer to form a plurality of first color filter films.

Claims 7-8 (canceled)

Claim 9. (currently amended) The method of claim 6, wherein the material layer has a thickness smaller than the first photoresist layer such that the filter material layer within the openings is separated from the filter material layer over the first photoresist layer.

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Claim 10. (original) The method of claim 6, wherein the material layer has a thickness equal to the first photoresist layer.